K-Resin® SBC KR53

Styrene Butadiene Block Copolymer

Chevron Phillips Chemical Company LLC

Message:

K-Resin® SBC KR53 is a Styrene Butadiene Block Copolymer (SBC) material. It is available in North America.
Important attributes of K-Resin® SBC KR53 are:
Clarity
Good Sealability
Good Toughness
High Gloss
Typical applications include:
Packaging
Film
Food Contact Applications
Labels
Medical/Healthcare

General Information	
Features	Good Heat Seal Good Toughness High Clarity High Gloss
Uses	Film Food Packaging Labels Medical/Healthcare Applications Packaging
Agency Ratings	EU 10/2011 FDA 21 CFR 177.1640

Physical	Nominal Value	Unit	Test Method
Specific Gravity	1.02	g/cm³	ASTM D792
Melt Mass-Flow Rate (MFR) (200°C/5.0 kg)	10	g/10 min	ASTM D1238
Films	**Nominal Value**	**Unit**	**Test Method**
Film Thickness - Tested	25	µm	
Secant Modulus			ASTM D882
1% Secant, MD : 25 µm, Blown Film	750	MPa	
1% Secant, TD : 25 µm, Blown Film	590	MPa	
Tensile Strength			ASTM D882
MD : Yield,25 µm, Blown Film	25.0	MPa	
TD : Yield,25 µm, Blown Film	20.0	MPa	
Tensile Elongation			ASTM D882

MD : Break, 25 µm,Blown Film	180	%	
TD : Break, 25 µm,Blown Film	180	%	
Dart Drop Impact (25 µm, Blown Film)	580	g	ASTM D1709
Elmendorf Tear Strength			ASTM D1922
MD : 25 µm, Blown Film	20	g	
TD : 25 µm, Blown Film	25	g	
Oxygen Permeability (25 µm, Blown Film)	110	$cm^3 \cdot mm/m^2/atm/24\ hr$	ASTM D3985
Water Vapor Transmission Rate (25 µm, Blown Film)	1.5	$g \cdot mm/m^2/atm/24\ hr$	ASTM F1249
Impact	**Nominal Value**	**Unit**	**Test Method**
Instrumented Dart Impact (0.0254 mm, Blown Film)	1.10	J	ASTM D3763
Thermal	**Nominal Value**	**Unit**	**Test Method**
Vicat Softening Temperature	62.8	°C	ASTM D1525
Optical	**Nominal Value**	**Unit**	**Test Method**
Gardner Gloss (25.4 µm, Blown Film)	140		ASTM D523
Haze (25.4 µm, Blown Film)	0.20	%	ASTM D1003

Recommended distributors for this material

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